

**Amendments to the Specification:**

**Please replace paragraph [0020] with the following amended paragraph:**

[0020] A thickness of the substrate section is not limited, but is preferably 50  $\mu\text{m}$  or less, more preferably 20  $\mu\text{m}$  or less and further preferably about 2 to 10  $\mu\text{m}$ , and it may have a cavity structure since the thin substrate works as a supporting member ~~to support the thin substrate~~. This thickness is based on a manufacturing method, and as described later, a material containing the titanium element beforehand is not used in the substrate section. When the titanium element is diffused from the electrode film by heat treatment, the above-described thickness is preferable for substantially uniformly diffusing the titanium element in the depth direction of the substrate section.